ABSTRACT OF THE DISCLOSURE

TITLE OF INVENTION: METHOD FOR FUSING AND FLATTENING BORON-PHOSPHURETED SILICATE GLASS FILM

A boron-phosphureted silicate glass film is heat treated under the condition that a value obtained by dividing the total gas flow in a heat treating furnace by a tube capacity in the heat treating furnace is 0.25 (1/min) or more. The boron-phosphureted silicate glass film is heat treated in an atmosphere of the mixed gas of hydrogen and nitrogen. Furthermore, the boron-phosphureted silicate glass film is heat treated in the gas atmosphere containing ammonia or a hydrogen compound (steam, a hydrogen peroxide solution, hydroxylamine and the like), or the mixed gas of the hydrogen compound and nitrogen. Thus, the boron-phosphureted silicate glass film is fused and flattened while inhibiting or eliminating the generation of a sludge of boron-phosphorus oxide.

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